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A scalable zinc-based coordination network for energy-efficient NF₃/CF₄ separation with unprecedented selectivity

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Nitrogen trifluoride (NF₃) and carbon tetrafluoride (CF₄) are critical gases in the semiconductor industry. However, their current lack of effective recycling and separation results in significant waste emissions, which are not only costly but also pose significant environmental challenges. Their separation remains a critical challenge due to their nearly identical physicochemical properties ($\Delta b p < 1$ °C, similar polarizability). Here, we demonstrate that a zinc-based metal–organic framework (CALF-20) with precisely tuned 4.8 Å pores achieves exceptional NF₃/CF₄ separation through molecular sieving. At 298 K, this material exhibits a record-high NF₃/CF₄ adsorption ratio of 41.1, and a CF₄ purity of 99.5% can be achieved through breakthrough experiments. Structural characterization and computational studies reveal that the unique pore channel properties preferentially adsorb NF₃ (kinetic diameter: 4.5 Å) while effectively excluding CF₄ (4.8 Å). This advance enables cost-effective gas purification at \$12.3 per kilogram, providing a practical solution for sustainable semiconductor manufacturing.

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Introduction

Following a decade of advancement, the global semiconductor market is projected to attain a valuation of one trillion dollars by the year 2030.¹ Fluorinated electronic specialty gases, including NF₃, CF₄ and other fluorinated gases, play an essential role in contemporary semiconductor manufacturing due to their distinctive chemical reactivity during plasma etching and cleaning processes.^{2,3} However, the semiconductor industry, which serves as a fundamental component of the global digital economy, is confronted with a growing environmental dilemma. The fluorinated process gases critical to semiconductor manufacturing – nitrogen trifluoride (NF₃) and carbon tetrafluoride (CF₄) – exhibit extraordinarily high global warming potentials (GWPs) of 17 200 and 6500 CO₂-equivalent,

respectively, with atmospheric lifetimes of 740 years for NF₃ and 50 000 years for CF₄.^{4,5} In the semiconductor manufacturing process, only a small portion of fluorinated gases are fully utilized, and a large amount of CF₄ and NF₃ exhaust gases remain stable after etching and cleaning, requiring high-temperature combustion or thermal plasma decomposition to effectively remove them.⁶ Despite the treatment of exhaust gases, these trace amounts of fluorine-containing compounds inevitably escape into the atmosphere through ventilation systems.⁷ The emissions of fluorinated gases from the global semiconductor industry are experiencing a year-on-year increase, which poses a considerable threat to the environment.^{8,9} The separation and recycling of NF₃ and CF₄ through advanced separation technologies not only enable their efficient recovery for industrial reuse—significantly reducing operational costs—but also promote optimal resource utilization. Importantly, this approach significantly mitigates F-gas emissions, substantially diminishing their environmental impact.

Current industrial recovery of fluorinated gases predominantly relies on cryogenic distillation and liquefaction techniques, which operate under energetically demanding high-pressure and low-temperature conditions.^{10,11} Porous adsorbent-based separation has emerged as an energy-efficient and economically viable strategy for the enrichment and recovery of high-value specialty gases. Porous materials—including zeolites,¹² activated carbons,^{13–15} metal–organic frameworks (MOFs),^{16,17} and porous organic cages—have demonstrated potential for fluorinated gas (F-gas) separation.

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However, while numerous traditional porous materials have been investigated for NF_3/N_2 and CF_4/N_2 separation, most reported adsorbents demonstrate limited selectivity for NF_3/CF_4 . The separation of NF_3 and CF_4 remains a significant challenge in gas purification due to their nearly identical kinetic diameters. The urgency to address this challenge is further emphasized by the pledge of the semiconductor industry to achieve net-zero emissions by 2050.¹⁸ This imperative demands the development of advanced materials that can effectively balance industrial scalability requirements with the need for molecular-level precision (Scheme 1).

MOFs have emerged as highly efficient adsorbents for gas separation, offering tunable pore geometries and chemical functionalities.¹⁹ Recent advances in ultra-microporous MOFs (pore size <7 Å) demonstrate exceptional selectivity for fluorinated gases (F-gases) *via* size exclusion and host-guest interactions. For instance, amino-functionalized $\text{NH}_2\text{-Ni-MOF}$ achieves a CF_4/N_2 selectivity of 46.3 through optimized van der Waals interactions,²⁰ while Co-MOF-74 exhibits NF_3/N_2 selectivity of 299.6 *via* Lewis acid-base interactions at open metal sites.²¹ Although some MOF materials have exhibited favorable performance in separating specific fluorinated gases, no MOF material has currently achieved effective sieving of NF_3/CF_4 . This is primarily due to the critical limitations inherent in MOF materials: (1) pore collapse during F-gas adsorption (*e.g.*, the M-MOF-74 series), whereas CALF-20 maintains high stability in both five cycles of static NF_3 adsorption and dynamic breakthrough experiments; (2) the failure of previous adsorbents to discriminate between NF_3 and CF_4 during adsorption processes, in contrast to CALF-20, which exhibits a record-high NF_3/CF_4 adsorption ratio of 41.1; (3) synthetic complexity that hinders scale-up, while CALF-20 is the first MOF material produced on an industrial scale. Achieving simultaneous high

selectivity, structural stability, and industrial viability remains a long-standing challenge.

Extensive research suggests that realizing efficient NF_3/CF_4 separation necessitates MOF materials with meticulously tailored pore dimensions and the exclusion of open metal sites. These rigorous specifications substantially narrow the scope of candidate materials. When stability requirements and cost considerations are additionally factored in, CALF-20 emerges as the most promising viable option currently available. The separation of NF_3 and CF_4 , key fluorinated gases in semiconductor manufacturing, poses a significant challenge due to their similar kinetic diameters. Despite extensive research on MOFs as potential adsorbents for gas separation, achieving efficient NF_3/CF_4 separation remains elusive. Existing MOF materials either lack the precise pore sizes required for molecular sieving or suffer from poor recyclability under industrial conditions, with many frameworks experiencing structural degradation after repeated adsorption cycles.

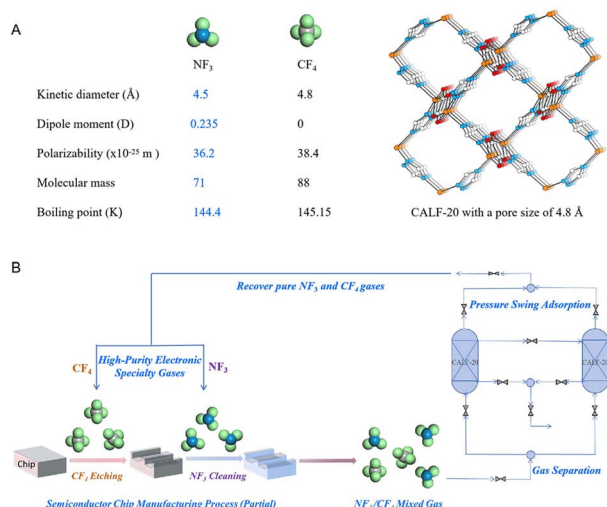
To address these limitations, this study focuses on developing scalable MOF adsorbents capable of molecular discrimination and practical recyclability for NF_3/CF_4 separation. Herein, we introduce CALF-20, an industrially viable MOF engineered with precisely tuned 4.8 Å ultra-micropores. By utilizing steric exclusion effects, CALF-20 is designed to overcome the long-standing challenge of separating NF_3 and CF_4 . Notably, this material exhibits a record-high NF_3/CF_4 selectivity of 41.1 and achieves >99.5% CF_4 purity in breakthrough experiments.

This work not only proposes a material design strategy for targeted gas separation but also demonstrates the potential of CALF-20 in enabling the recovery of NF_3 and CF_4 through PSA systems. Such an approach offers a sustainable pathway for the energy-efficient recovery of fluorinated gases, in line with the goal of the semiconductor industry to achieve net-zero emissions by 2050.²²

Results and discussion

Adsorption performance of CALF-20 for NF_3

CALF-20 is constructed from zinc(II) ion layers interconnected by 1,2,4-triazole ligands and oxalate ion ligand pillars.²³ In recent years, numerous studies on gas separation systems related to CALF-20 have been published,^{24–26} and we have also explored its adsorption properties.^{27,28} However, there has been no prior report on CALF-20 for the adsorption of NF_3 and CF_4 . This study represents the first investigation into the adsorption and separation performance of CALF-20 for NF_3/CF_4 . As a robust adsorbent for NF_3 capture, CALF-20 demonstrates exceptional structural integrity and cycling stability under various operational conditions (Fig. 1). The temperature-dependent adsorption isotherms (273–313 K) reveal a characteristic Type I physisorption behavior, with NF_3 uptake capacity increasing systematically from $32.1 \text{ cm}^3 \text{ g}^{-1}$ at 313 K to $51.1 \text{ cm}^3 \text{ g}^{-1}$ at 273 K, following expected thermodynamic trends (Fig. 1A). Remarkably, five consecutive adsorption–desorption cycles at 298 K (Fig. 1B) show outstanding reproducibility, with NF_3 working capacity maintained at $37.4 \pm 0.7 \text{ cm}^3 \text{ g}^{-1}$ (variation



Scheme 1 (A) A comparison of some physical parameters of NF_3 and CF_4 and the pore structure of CALF-20. (B) The NF_3/CF_4 mixture in semiconductor manufacturing is efficiently separated, purified, and recycled through a pressure swing adsorption (PSA) device packed with CALF-20.



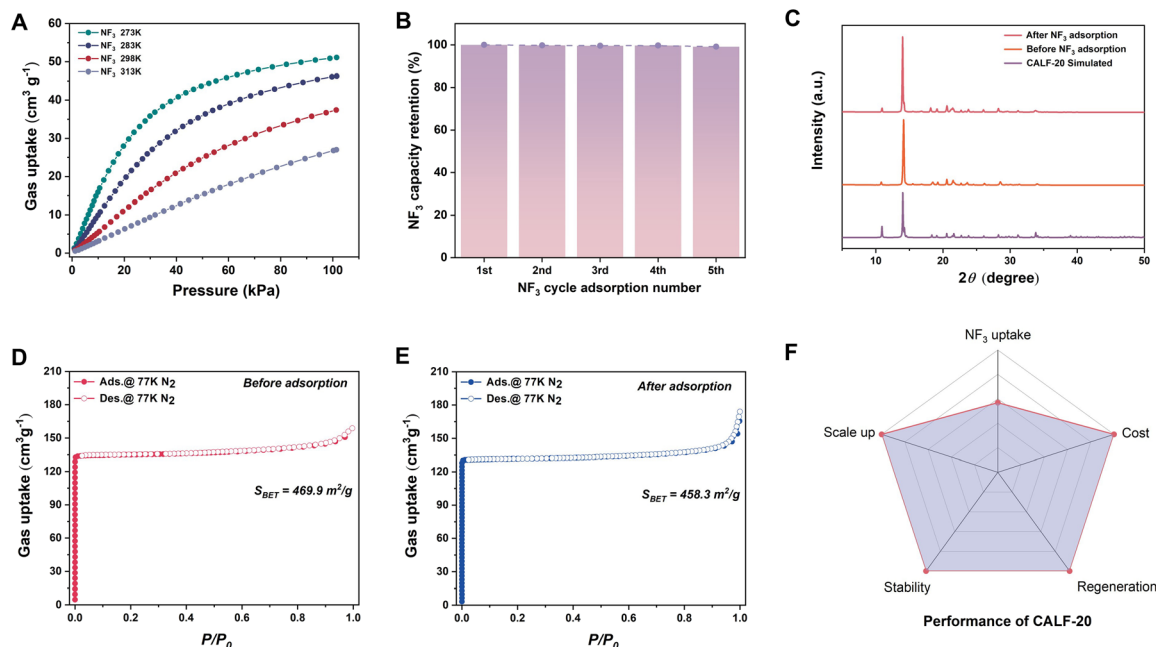


Fig. 1 Adsorption properties and cycling stability of CALF-20 for NF_3 capture. (A) The NF_3 adsorption isotherms on CALF-20 at different temperatures. (B) Capacity retention performance of NF_3 cycle adsorption. (C) The PXRD pattern of CALF-20 before and after NF_3 adsorption. (D) The N_2 sorption isotherms at 77 K before NF_3 adsorption. (E) The N_2 sorption isotherms at 77 K after NF_3 adsorption. (F) The five-criteria radar chart of the CALF-20.

<2%), demonstrating excellent cycling stability that meets industrial requirements for long-term operation. Notably, CALF-20 demonstrates exceptional stability toward NF_3 – a unique characteristic unmatched by other MOF materials. To our knowledge, it represents the first MOF capable of maintaining consistent NF_3 adsorption performance through multiple cycles without observable performance degradation. Comprehensive characterization further confirms the structural robustness of the framework. The PXRD patterns (Fig. 1C) display identical peak positions and intensities both before and after NF_3 exposure. There is no observable peak broadening, and no new phases emerge, which indicates that the crystallinity is completely retained. N_2 physisorption measurements (Fig. 1D and E) show minimal changes in porosity, with BET surface area decreasing only slightly from $467 \text{ m}^2 \text{g}^{-1}$ to $458 \text{ m}^2 \text{g}^{-1}$ (<2.5% reduction) and pore volume remaining essentially unchanged ($0.38 \text{ cm}^3 \text{g}^{-1}$ vs. $0.37 \text{ cm}^3 \text{g}^{-1}$), suggesting negligible pore damage or structural collapse. These results are supplemented by a five-dimensional performance evaluation (Fig. 1F) that quantitatively assesses the balanced characteristics of CALF-20, including its high NF_3 uptake capacity (performance), excellent cycling stability (stability), mild regeneration conditions (regeneration), scalable synthesis (cost), and wide operating temperature range (scale up).

The combined evidence from these systematic characterizations establishes CALF-20 as a structurally durable and practically viable adsorbent for industrial NF_3 separation processes, offering significant advantages over traditional materials in terms of both performance and operational stability. The ability of the material to maintain its adsorption capacity and

structural integrity under repeated cycling, coupled with its temperature-dependent tunability, positions it as a promising candidate for pressure-swing adsorption applications in fluorocarbon purification.

Molecular sieving for efficient NF_3/CF_4 separation

CALF-20 exhibited negligible adsorption of CF_4 across the temperature range of 273–313 K. Adsorption isotherms at 298 K establish CALF-20 as a near-ideal molecular sieve, exhibiting complete exclusion of CF_4 (uptake $<1 \text{ cm}^3 \text{g}^{-1}$) while achieving suitable NF_3 capacity ($37.4 \text{ cm}^3 \text{g}^{-1}$ at 100 kPa) (Fig. 2A). Our study reveals that CALF-20 exhibits unique temperature-dependent molecular sieving properties. Across a broad temperature range (273–313 K), the material consistently demonstrates complete exclusion of CF_4 while maintaining stable NF_3 uptake (Fig. 2B). A moderate temperature decrease from 298 K to 273 K at 100 kPa does not significantly increase CF_4 adsorption capacity, but significantly enhances NF_3 adsorption capacity to $51.1 \text{ cm}^3 \text{g}^{-1}$, representing an increase of approximately 36.6% compared to the uptake at 298 K (Fig. 2C).

CALF-20 exhibits an exceptional NF_3/CF_4 adsorption ratio of 41.1 at 298 K (Fig. 2D), significantly surpassing all the previously reported porous materials including ATC-Cu (1.46),²⁹ HKUST-1 (1.18),²⁰ Cu(peba)₂ (1.07),²⁰ Ni(pba)₂ (0.83),²⁰ Ni-MOF (0.91),²⁰ NH_2 -Ni-MOF (1.08),²⁰ $\text{Co}_3(\text{HCOO})_6$ (1.03),³⁰ $\text{Ni}_3(\text{HCOO})_6$ (1.33),³⁰ $\text{Mn}_3(\text{HCOO})_6$ (1.84)³⁰ and SBMOF-1 (1.16).³¹ This outstanding separation performance is of great significance in the field of fluorocarbon separation, as it can potentially revolutionize the industrial separation processes of NF_3/CF_4 mixtures, reducing energy consumption and improving separation efficiency. This



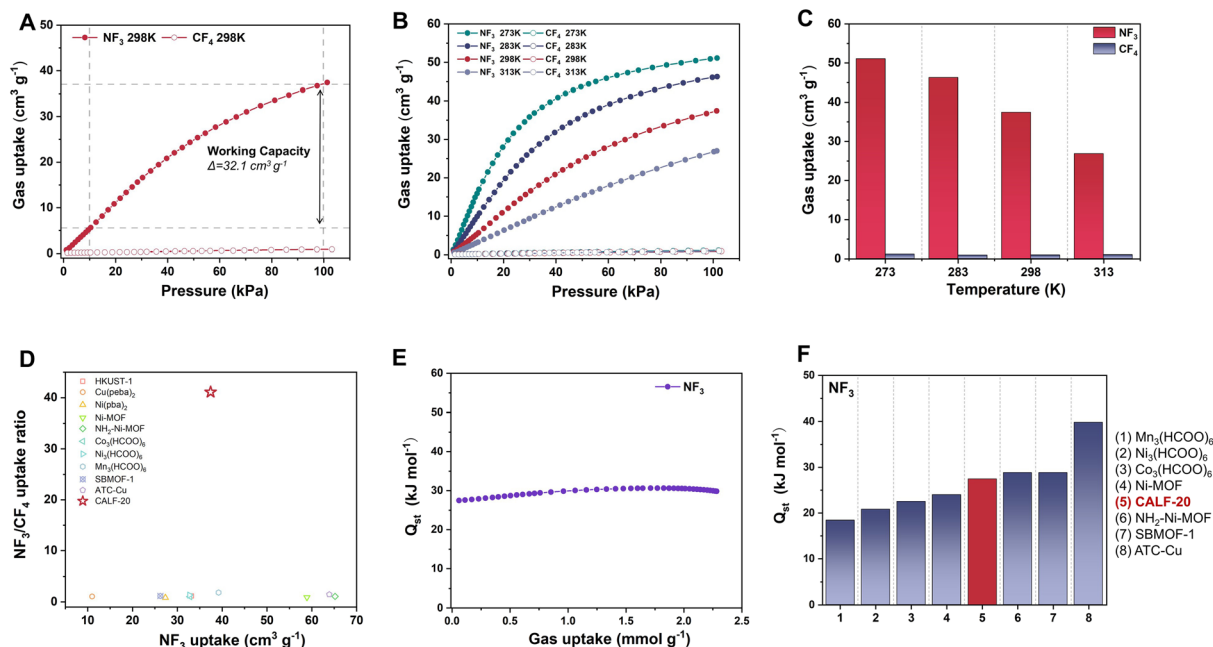


Fig. 2 Molecular sieving and thermodynamic analysis of NF₃/CF₄ separation in CALF-20. (A) The NF₃ and CF₄ adsorption isotherms of CALF-20 at 298 K. (B) The NF₃ and CF₄ adsorption isotherms of CALF-20 at different temperatures. (C) Adsorption capacity of CALF-20 for NF₃ and CF₄ at 100 kPa and different temperatures. (D) NF₃ uptakes and NF₃/CF₄ uptake ratio comparison with some reported materials at 298 K and 100 kPa. (E) Isothermic heats of adsorption (Q_{st}) of NF₃. (F) The calculated NF₃ Q_{st} of CALF-20 and other reported materials.

remarkable enhancement in separation performance demonstrates the unique molecular sieving capability of CALF-20 for NF₃/CF₄ mixtures. While other MOFs show adsorption ratios clustered near the vapor–liquid equilibrium prediction (~ 1.25), CALF-20 achieves a 28-fold improvement over the previous best performer (ATC-Cu), establishing new benchmarks for fluorocarbon separations. The superior performance originates from the precisely tuned pore structure of CALF-20. This pore structure enables complete exclusion of CF₄ while maintaining an effective NF₃ adsorption capacity. The isosteric heat of adsorption (Q_{st}) for NF₃ in CALF-20 was determined to be 27.5 kJ mol⁻¹ at zero coverage (Fig. 2E), calculated from gas adsorption isotherms over 273–313 K. This intermediate binding strength represents an optimal balance for practical applications: sufficiently strong to ensure effective NF₃ capture at ambient conditions, yet weak enough to permit energy-efficient regeneration (Fig. 2F). Compared with other materials, this unique adsorption energy characteristic endows CALF-20 with distinct advantages in terms of adsorption efficiency and regeneration performance, which is crucial for its large-scale industrial application.

Diffusion barriers and host–guest interactions of NF₃/CF₄ in CALF-20

Minimum energy path (MEP) calculations reveal fundamentally different diffusion mechanisms for NF₃ and CF₄ during adsorption in the channels of CALF-20. The energy profile shows that NF₃ encounters a moderate activation barrier of 65.6 kJ mol⁻¹ at the channel bottleneck (position-6, Fig. 3A and

B), while CF₄ faces a substantially higher barrier of 111.7 kJ mol⁻¹ (position-5, Fig. 3D and E) – consistent with its larger kinetic diameter (4.8 Å vs. 4.5 Å for NF₃). Furthermore, an analysis of host–guest interaction distances reveals that CF₄ exhibits stronger interactions (H \cdots F: 2.60–3.69 Å) compared to NF₃ (H \cdots F: 2.64–4.03 Å) (Fig. S5), which underscores the steric hindrance associated with its molecular structure.

Synergistic analysis of breakthrough experiments and *in situ* infrared spectroscopy

The separation mechanism is synergistically verified by combining the macroscopic separation performance from breakthrough experiments with the microscopic interaction mechanism revealed by *in situ* infrared spectroscopy. In order to evaluate the separation capabilities of CALF-20 for NF₃/CF₄ mixtures, we conducted dynamic breakthrough experiments at a temperature of 298 K utilizing an equimolar (50/50, v/v) NF₃/CF₄ gas mixture. The gas was introduced at a flow rate of 6 mL min⁻¹ through a packed column filled with the activated adsorbent. Breakthrough experiments reveal instantaneous CF₄ permeation (retention time = 1.3 min g⁻¹) versus strong NF₃ retention (5.3 min g⁻¹) in CALF-20, demonstrating its molecular sieving selectivity for NF₃/CF₄ separations (Fig. 4A). Five consecutive breakthrough cycles demonstrate the stable NF₃/CF₄ separation performance of CALF-20. The retention times are nearly identical, which confirms the recyclability of CALF-20 for industrial gas purification (Fig. 4B). Temperature-dependent breakthrough measurements reveal enhanced NF₃/CF₄ separation at 273 K and 283 K, with NF₃ retention time increasing by

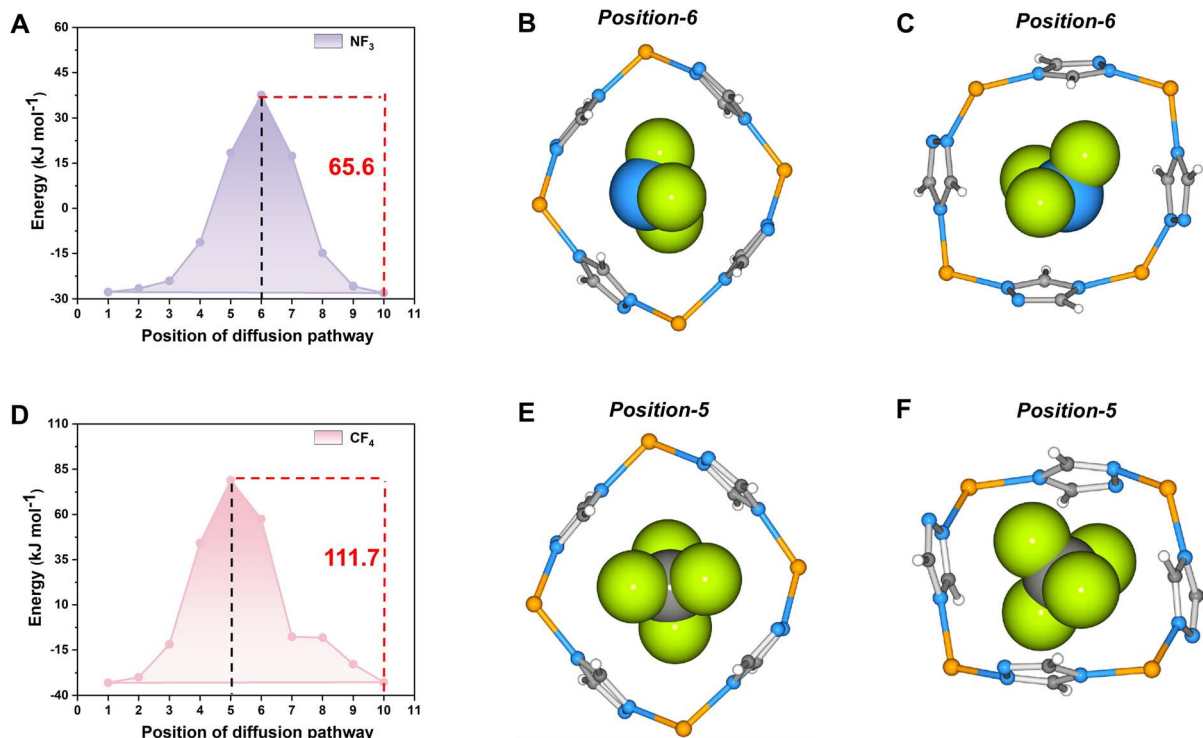


Fig. 3 DFT calculations. Energy profiles for NF_3 (A) and CF_4 (D) diffusion in CALF-20; molecular configuration at the positions with maximum energy for NF_3 (B and C) and CF_4 (E and F) in CALF-20.

52% and 96% (from 5.3 to 8.1 and 10.2 min g^{-1}) while maintaining the instantaneous permeation of CF_4 , indicating that reducing the temperature appropriately will not significantly

increase energy consumption, but will significantly enhance the separation performance of NF_3/CF_4 (Fig. 4C). Regeneration studies at 298 K using He purge gas (6 mL min^{-1}) revealed

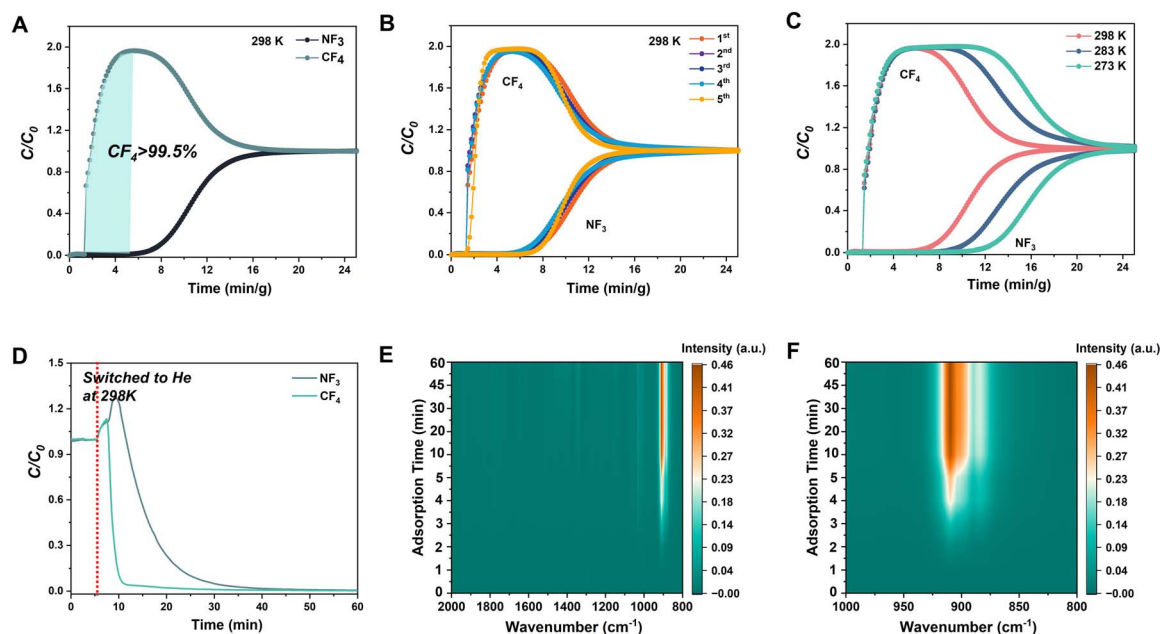


Fig. 4 The breakthrough performance and *in situ* infrared spectroscopy of CALF-20. (A) The NF_3/CF_4 breakthrough curve of CALF-20 at 298 K (adsorption condition: NF_3/CF_4 v/v 50/50 with the flow rate of 6 mL min^{-1}). (B) Five cycles of column breakthrough experiments. (C) The NF_3/CF_4 breakthrough curves of CALF-20 at different temperatures. (D) Desorption curves by He purge with the flow rate of 6 mL min^{-1} at 298 K. (E) *In situ* 3D DRIFTS spectral mapping of 1% NF_3 adsorption on CALF-20 from 0–60 min. (F) *In situ* DRIFTS mapping showing localized N–F bond perturbations (910 cm^{-1}).

distinct desorption kinetics where CF_4 was rapidly eluted, while NF_3 exhibited prolonged retention. This directly demonstrates that CALF-20 had a stronger affinity for NF_3 at room temperature (Fig. 4D). To investigate the interaction mechanism between NF_3 and CALF-20, we employed *in situ* FTIR spectrum to monitor real-time vibrational changes during NF_3 adsorption. Within the 2000–800 cm^{-1} range, the FTIR spectrum exhibited only the N–F asymmetric stretching vibration of NF_3 at 910 cm^{-1} (Fig. 4E). *In situ* FTIR spectroscopy of NF_3 adsorbed in CALF-20 exhibited an unshifted N–F asymmetric stretching vibration at 910 cm^{-1} (Fig. 4F), which is identical to the infrared resonance peak reported in the references for pure NF_3 gas measurements.³² This observation suggests that the interaction between NF_3 and CALF-20 is weak and primarily governed by physisorption. Besides, the 3D DRIFTS spectra recorded during desorption (Fig. S6) showed a symmetric decrease in the 910 cm^{-1} band intensity, mirroring the adsorption profile and confirming the reversibility of NF_3 uptake—an essential attribute for practical PSA applications. This reversibility, coupled with the sustained framework integrity (no new peaks or shifts in XRD patterns during multiple adsorption–desorption cycles), further underscores the structural stability of CALF-20 under operational conditions.

Combining the different diffusion energy barriers obtained from our DFT calculations (65.6 kJ mol^{-1} vs. 111.7 kJ mol^{-1}) and breakthrough data demonstrating high NF_3/CF_4 selectivity, we conclude that molecular sieving in CALF-20 is governed primarily by sieving rather than differential adsorption affinity. The retention of the vibrational signature of NF_3 further confirms the structural stability of the framework during NF_3 gas uptake.

Conclusion

In summary, CALF-20, a metal–organic framework with precisely engineered 4.8 Å pores, has emerged as a breakthrough solution for the separation of nitrogen trifluoride (NF_3) and carbon tetrafluoride (CF_4) in semiconductor manufacturing. This material achieves an NF_3/CF_4 uptake ratio of 41.1 and can produce CF_4 with a purity of >99.5% through breakthrough experiments at 298 K, setting a new benchmark for fluorocarbon separation. The unique pore structure of CALF-20 enables selective molecular sieving of NF_3 (kinetic diameter: 4.5 Å) while effectively excluding CF_4 (4.8 Å), as confirmed by structural characterization and computational studies. The remarkable stability and recyclability of the framework over multiple adsorption cycles, combined with its mild regeneration conditions and scalable synthesis, position it as a practical and cost-effective choice for industrial gas purification. This work not only addresses a critical environmental and economic challenge in the semiconductor industry but also provides a model for developing advanced porous materials that can achieve high selectivity and stability for challenging gas separations. By providing a viable way for the energy-efficient recovery of electronic special gases, CALF-20 supports the transition of the semiconductor sector to sustainable practices and the goal of achieving net-zero emissions by 2050.

Author contributions

Q.-Y. Y. initiated and supervised the research. Q.-Y. Y. and Y.-T. L. designed the project and experiments. Y.-T. L. performed the adsorbents preparation and gas adsorption experiments. L.W.L. and L.X.X. performed the simulated calculations. Y.-Y. G., T.-Y. Z. and N. G. performed *in-situ* infrared spectroscopy measurements. Q.-Q. G. provided financial support for the study. L.-P. Z., L. X., S.-M. W., and Q.-Y. Y. discussed the experimental results and provided valuable suggestions. Y.-T. L. wrote the manuscript. Q.-Y. Y. performed manuscript edits and revisions. All authors contribute to the final manuscript and the interpretation of the results.

Conflicts of interest

There are no conflicts to declare.

Data availability

Additional details regarding the experimental and calculation data are given in the SI, including *in situ* infrared purging data in Fig. S1–S6 and Table S1 and S2. See DOI: <https://doi.org/10.1039/d5sc04966k>.

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